



## U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE

Information Disclosure  
Statement

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GROUP:

## U.S. PATENT DOCUMENTS

Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date
MK	6,015,761	01/18/00	Merry	438/727	438/723	6/26/96
MK	6,055,927	05/02/00	Shang	118/723MI	118/723E	1/14/97
MK	4,867,841	9/19/89	Loewenstein	156/643	156/646	5/27/88

## FOREIGN PATENT OR PUBLISHED FOREIGN PATENT APPLICATION

Publication: Patent Cooperation Treaty (PCT)  
Translation: English  
Document Number: 03077786 Date: 4/10/91 ✓  
Country: Japan  
Class Or Subclass C23C 16/44  
Patent: Yes \_ No X  
Title: Film Forming Device Provided with Deposit Recovering Device

Publication: Patent Cooperation Treaty (PCT)  
Translation: English  
Document Number: 0429 809 A2 Date: 10/10/90 ✓  
Country: Germany  
Class Or Subclass H01L 21/00  
Patent: Yes \_ No X  
Title: Method and Apparatus for Etching Semiconductor Materials

Publication: Patent Cooperation Treaty (PCT)  
Translation: English  
Document Number: WO 99/02754 Date: 1/21/99 ✓  
Country: Greate Britain  
Class Or Subclass C23C 16/44  
Patent: Yes \_ No X  
Title: Remote Plasma Celaning Apparatus

## OTHER DOCUMENTS (Including Author, Title, Place of Date, Publication)

Examiner

Date Considered

12/10/02

EXAMINER: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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